

Abstract Submitted  
for the MAR10 Meeting of  
The American Physical Society

**Arrangement of block copolymer microdomains confined at hemispherical substrates with different brush layers** DU SIK BAE, WON CHUL JOO, JIN SEOK BYUN, GUMHYE JEON, JIN KON KIM — The arrangement of the microdomains in block copolymers changes significantly from that in bulk, when they are confined at certain geometric constraints. Although many research works have been reported on microdomain arrangement at one-dimension, two-dimension, and three-dimension confinement, the hemispherical geometry has been never employed for this purpose. Here, we study, via scanning and transmission electron microscopy, the arrangement of the microdomains of polystyrene-block-poly(methyl methacrylate) copolymer (PS-*b*-PMMA) confined at a hemispherical wall. This constraint was introduced by using anodic aluminum oxide template. The inner wall surface of the hemispherical wall was further modified by three different brush layers: (1) PS, (2) PMMA, and (3) neutral brushes on PS and PMMA. We observed some interesting morphologies which have not been reported.

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Date submitted: 18 Nov 2009

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